

December 4, 2015
Sony Corporation

Sony and Toshiba Sign Definitive Agreements for the Transfer of Semiconductor Fabrication
Facilities

Tokyo, Japan, December 4th, 2015 – Sony Corporation made the announcement noted above. For further detail, please refer to the attached English press release.

This transaction is not anticipated to have a material impact on Sony's consolidated financial results for the fiscal year ending March 31, 2016.

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Toshiba Corporation

Sony and Toshiba Sign Definitive Agreements for the Transfer of Semiconductor Fabrication Facilities

Tokyo, Japan, December 4th, 2015 -- Based on the memorandum of understanding entered into between Sony Corporation ("Sony") and Toshiba Corporation ("Toshiba") on October 28, 2015, the parties today announced that they have signed definitive agreements to transfer to Sony and to Sony Semiconductor Corporation ("SCK"), a wholly-owned subsidiary of Sony, certain Toshiba-owned semiconductor fabrication facilities, equipment and related assets in its Oita Operations facility, as well as other related equipment and assets owned by Toshiba (the "Transfer").

Under the agreements, Toshiba will transfer semiconductor fabrication facilities, equipment and related assets of Toshiba's 300mm wafer production line, mainly located at its Oita Operations facility. The purchase price of the Transfer is 19 billion yen. Sony and Toshiba aim to complete the Transfer within the fiscal year ending March 31, 2016, subject to any required regulatory approvals.

Following the Transfer, Sony and SCK plan to operate the semiconductor fabrication facilities as fabrication facilities of SCK, primarily for manufacturing CMOS image sensors.

The parties expect to offer the employees of Toshiba and its affiliates employed at the fabrication facilities to be transferred, as well as certain employees involved in areas such as CMOS image sensor engineering and design (approximately 1,100 employees in total), employment within the Sony Group, upon the completion of the Transfer.

Outline of 300mm wafer fabrication facilities, Toshiba Oita Operations

Building completion: February, 2004

Location: 3500 Oaza Matsuoka, Oita City, Oita Prefecture, Japan

Building area: 24,100 m²

Total floor space: 48,800 m²

Main products: CMOS image sensors, memory controllers